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ATTORNEY DOCKET NO. 10031375-1

AGILENT TECHNOLOGIES, INC.
Legal Department, DL429
Intellectual Property Administration
P. O. Box 7599
Loveland, Colorado 80537-0599

JUN 0 8 2005

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor(s): Ken A. Nishimura et al.

Serial No.: 10/736,724

1

Examiner: Hung Nguyen

Filing Date: December 15, 2003

Group Art Unit: 2851

Title: DEFECT MITIGATION IN SPATIAL LIGHT MODULATOR USED FOR

DYNAMIC PHOTOLITHOGRAPHY

COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria VA 22313-1450

TRANSMITTAL LETTER FOR RESPONSE/AMENDMENT

Si	r:									
Tra	ansmitted he	erewith is/are the follo	wing in the	above-identified a	applica	tion:				
×	Response/Amendment				Petition to extend time to respond					
	New fee a	as calculated below		Supplemental Declaration						
×	No additional fee (Address envelope to "Mail Stop Amendments")									
×	Other: Tv	Other: Two Postcards (Fee \$)								
Γ		CLAIMS	L ENTITY							
	(1) FOR	(2) CLAIMS REMAINING AFTER AMENDMENT	(3) NUMBER EXTRA	(4) HIGHEST NUMBE PREVIOUSLY PAID		(5) PRESENT EXTRA	(6) RATE	ADDI	7) FIONAL EES	
Ī	TOTAL CLAIMS	25	MINUS	25		= 0	X 50	\$	0	
	INDEP. CLAIMS	4	MINUS	4		= 0	X 200	\$	0	
Ī	TEIRST PRI	ESENTATION OF A MULT	IPLE DEPEN	DENT CLAIM	<u> </u>		+ 360	\$	0	

2ND MONTH

450.00

Charge \$0 ____ to Deposit Account **50-1078**. At any time during the pendency of this application, please charge any fees required or credit any over payment to Deposit Account **50-1078** pursuant to 37 CFR 1.2 5. Additionally please charge any fees to Deposit Account **50-1078** under 37 CFR 1.16, 1.17, 1.19, 1.20 and 1.21. A duplicate copy of this transmittal letter is enclosed.

3RD MONTH

1020.00

TOTAL ADDITIONAL FEE FOR THIS AMENDMENT

I hereby certify that this correspondence is being Deposited with the United States Postal Service as First class mail in an envelope addressed to: Commissioner for Patents, PO Box 1450, Alexandria, VA 22313-1450.

1ST MONTH

120.00

Date of Deposit: June 2, 2005

Typed Name: Phil Rudnick

EXTENSION

FEE

Signature: ////////

Respectfully submitted,

Ken A. Nishimura et al.

4TH MONTH

1590.00
OTHER FEES

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Holly L. Rydnick
Attorney/Agent for Applicant(s)

Reg. No. 43,065

Date: June 2, 2005

Telephone No. 214-387-8097



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In the Applica	ation of:							
Ken A. Nishimura, et al.)) Examiner: Hung Nguyen						
Serial No.	10/736,724) Group Art Unit: 2851						
Filed:	December 15, 2003							
For: DEFECT MITIGATION IN SPATIAL LIGHT MODULATOR USED FOR DYNAMIC PHOTOLITHOGRAPHY								
Commissione P. O. Box 145		CERTIFICATE OF MAILING I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to Mail Stop Amendment, Commissioner for Patents, P. O. Box 1450, Alexandria, VA 22313-1450						
		Date of Deposit: June 2, 2005						

Dear Sir:

RESPONSE TO RESTRICTION REQUIREMENT

A Restriction Requirement was issued in the present patent application on May 20, 2005, with a shortened time period for responding ending on June 20, 2005.

The Restriction Requirement identified the following groups of the claimed invention:

Group I:

Claims 1-10, drawn to a process

Group II:

Claims 11-25, drawn to an apparatus

In response to the Restriction Requirement, the Applicants provisionally elect the claims of Group II for prosecution on the merits WITH TRAVERSE.

The Restriction Requirement states that the inventions in Group I and Group II are related as a process and apparatus for its practice. The Restriction Requirement further cites MPEP 806.05(e) as providing the basis for determining distinctiveness between Group I and Group II. Specifically, MPEP 806.05(e) requires the Examiner to demonstrate that either (1) the process as claimed can be practiced by another materially different apparatus or by hand; or (2) the apparatus as claimed can be used to practice another and materially different process to show distinctiveness between Group I and Group II. The Applicants respectfully submit that the Examiner has not made such a showing.

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In section 2 of the Restriction Requirement, the Examiner stated that the apparatus as claimed in Claims 11-25 can be used to practice another and materially different process, such as a process for fabricating a semiconductor integrated circuit device and a spatial light modulator inspection method. However, the process claimed in Claims 1-10 is merely a "method for performing photolithography," which is inherently included in a semiconductor integrated circuit fabrication process or an inspection process practiced using the "photolithography apparatus" claimed in Claims 11-25. Thus, the processes of "fabricating semiconductor integrated circuit devices" and "spatial light modulator inspection method" are not processes materially different from the "photolithography" process claimed in Claims 1-10.

As a result, the Examiner has not demonstrated that the photolithography apparatus claims (Claims 11-25) can be used to practice a process materially from the "method for performing photolithography" claimed in Claims 1-10. Therefore, the Applicants respectfully request the Examiner to withdraw the restriction requirement.

Docket No. 10031375-1 Serial No. 10/736,724 (AGIL01-00219)

If any issue arises, or if the Examiner has any suggestions for expediting allowance of this application, the Applicant respectfully invites the Examiner to contact the undersigned at the telephone number indicated below or at *hrudnick@texaspatents.com*.

Respectfully submitted,

Registration No. 43,065

KEN A. NISHIMURA, ET AL.

Date: 6/2/2005

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